

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :
Inventor(s): Sun Woon KIM et al. :
U.S. Patent Application No.: *Not yet assigned* : Group Art Unit: *Not yet assigned*
Filed: *Herewith* :
For: FABRICATION METHOD OF NITRIDE SEMICONDUCTORS AND NITRIDE
SEMICONDUCTOR STRUCTURE FABRICATED THEREBY

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

The attached references appear in the specification.

Respectfully submitted,

LOWE HAUPTMAN GILMAN & BERNER, LLP

Benjamin J. Hauptman
Registration No. 29,310

1700 Diagonal Road, Suite 300
Alexandria, Virginia 22314
(703) 684-1111
Facsimile: (703) 518-5499
Date: March 23, 2004
BJH/ayh

**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION
(PTO-1449)**

ATTY. DOCKET NO.
2336-254

U.S. APPLICATION NO.
Not yet assigned

APPLICANT
Sun Woon KIM et al.

FILING DATE
herewith

GROUP
Not yet assigned

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,290,393	03/1994	Nakamura			
	6,528,394	03/2003	Lee			

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	2000-0055374	09/2000	Republic of Korea				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.